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			Application Number	10/709,054		
TRANSMITTAL			Filing Date	04/09/2004		
	FORM		First Named Inventor	Shao-Kang Chang		
(to be used for a	all coπespondence after initial i	filing)	Art Unit			
			Examiner Name			
Total Number of	Pages in This Submission	3	Attorney Docket Number	NTCP0019U	JSA	
		ENCI	OSURES (Check all tha	t apply)		
Amendme Af Af Af Af Extension Express A Informatio Certified C Document Response Incomplet	ifidavits/declaration(s) of Time Request bandonment Request on Disclosure Statement Copy of Priority		Drawing(s) Licensing-related Papers Petition Petition to Convert to a Provisional Application Power of Attorney, Revocation Change of Correspondence Addr Terminal Disclaimer Request for Refund CD, Number of CD(s) ks	ess	to Technolo Appeal Cor of Appeals Appeal Cor (Appeal Noti Proprietary Status Lette	osure(s) (please
	SIGNA	TURE C	F APPLICANT, ATTORN	EY, OR A	GENT	
Firm or Individual name Signature Winston Hsu, Reg. No.: 41,526 Signature Out of Individual name Signature Out of Individual name						
4111/1004						
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Typed or printed name						
Signature					Date	

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PTO/SB/17 (10-03) Approved for use through 07/31/2006. OMB 0651-0032 U.S. Patent and Trademark Office; U.S. DEPARTMENT OF COMMERCE Under De aperwork Reduction Act of 1995, no persons are required to respond to a collection of information unless it displays a valid OMB control number.

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TOTAL AMOUNT OF PAYMENT

CEE TO A NICHITTAI	Complete if Known		
FEE TRANSMITTAL	Application Number	10/709,054	
for FY 2004	Filing Date	2004/4/9	
Effective 10/01/2003. Patent fees are subject to annual revision.	First Named Inventor	Shao-Kang Chang	
1	Examiner Name		
Applicant claims small entity status. See 37 CFR 1.27	Art Unit		

NTCP0019USA Attorney Docket No. METHOD OF PAYMENT (check all that apply) FEE CALCULATION (continued) 3. ADDITIONAL FEES Credit card Money Check Other None Order Large Entity _I Small Entity Deposit Account: Fee Fee Fee Fee Fee Description Deposit Code (\$) Code (\$) <u>Fee Paid</u> 50-0801 Account 1051 130 2051 65 Surcharge - late filing fee or oath Number Deposit 50 2052 25 Surcharge - late provisional filing fee or 1052 North America International Patent Office Account cover sheet Name 130 Non-English specification 1053 130 1053 The Director is authorized to: (check all that apply) 1812 2,520 For filing a request for ex parte reexamination 1812 2,520 Charge fee(s) indicated below Credit any overpayments 920* Requesting publication of SIR prior to 1804 9201 1804 ✓ Charge any additional fee(s) or any underpayment of fee(s). **Examiner action** Charge fee(s) indicated below, except for the filing fee 1805 1,840* Requesting publication of SIR after 1805 1,8401 **Examiner action** to the above-identified deposit account. 1251 110 2251 Extension for reply within first month **FEE CALCULATION** 2252 210 Extension for reply within second month 1252 420 1. BASIC FILING FEE 1253 950 2253 475 Extension for reply within third month Large Entity Small Entity Fee Fee Fee Fee Fee Paid Fee Description 1254 1,480 2254 740 Extension for reply within fourth month Code (\$) Code (\$) 1,005 Extension for reply within fifth month 1255 2,010 2255 1001 770 2001 385 Utility filing fee 330 1401 2401 165 Notice of Appeal 1002 340 2002 170 Design filing fee 1402 330 2402 165 Filing a brief in support of an appeal 1003 530 2003 265 Plant filing fee 1403 290 2403 145 Request for oral hearing 1004 770 2004 385 Reissue filing fee 1451 1,510 1005 160 2005 80. Provisional filing fee 1451 1,510 Petition to institute a public use proceeding 1452 110 2452 55 Petition to revive - unavoidable **SUBTOTAL (1)** (\$) 0.00 1453 1,330 665 Petition to revive - unintentional 2. EXTRA CLAIM FEES FOR UTILITY AND REISSUE 1501 1,330 2501 665 Utility issue fee (or reissue) Fee from Fee Paid Extra Claims below 1502 480 2502 240 Design issue fee **Total Claims** -20** = 1503 640 2503 320 Plant issue fee Independent - 3** = Claims 1460 130 1460 130 Petitions to the Commissioner Multiple Dependent 1807 50 1807 50 Processing fee under 37 CFR 1.17(a) Large Entity | Small Entity 180 Submission of Information Disclosure Stmt 1806 180 1806 Fee Fee Fee Fee **Fee Description** 40 Recording each patent assignment per Code (\$) Code (\$) 8021 8021 40 property (times number of properties) Claims in excess of 20 1202 18 2202 9 770 385 Filing a submission after final rejection 1809 2809 Independent claims in excess of 3 1201 86 2201 43 (37 CFR 1.129(a)) Multiple dependent claim, if not paid 1203 290 2203 145 385 For each additional invention to be 1810 770 2810 examined (37 CFR 1.129(b)) ** Reissue independent claims 2204 43 1204 86 over original patent 770 1801 2801 385 Request for Continued Examination (RCE) ** Reissue claims in excess of 20 1802 900 1802 900 Request for expedited examination 1205 18 2205 9 and over original patent of a design application Other fee (specify) (\$) 0.00SUBTOTAL (2) *Reduced by Basic Filing Fee Paid SUBTOTAL (3) (\$) 0.00 **or number previously paid, if greater; For Reissues, see above SUBMITTED BY (Complete (if applicable))

Registration No. Winston Hsu Name (Print/Type) 41,526 Telephone 886289237350 (Attorney/Agent) Signature Date

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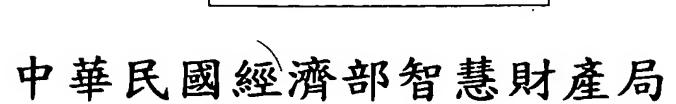
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DECLARATION — Supplemental Priority Data Sheet

Additional foreign applications:					
Prior Foreign Application Number(s)	Country	Foreign Filing Date (MM/DD/YYYY)	Priority Not Claimed	Certified Copy YES	Attached?
092128338	Taiwan R.O.C	10/13/2003			
•		•			

Burden Hour Statement: This form is estimated to take 21 minutes to complete. Time will vary depending upon the needs of the individual case. Any comments on the amount of time you are required to complete this form should be sent to the Chief Information Officer, U.S. Patent and Trademark Office, Washington, DC 20231. DO NOT SEND FEES OR COMPLETED FORMS TO THIS ADDRESS. SEND TO: Assistant Commissioner for Patents, Washington, DC 20231.





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茲證明所附文件,係本局存檔中原申請案的副本,正確無訛,其申請資料如下:

This is to certify/that annexed is a true copy from the records of this office of the application as originally filed which is identified hereunder:

申 請 日: 西元 2003 年 10 月 13 日 Application Date

申 請 案 號: 092128338

Application No.

申 請 人:南亞科技股份有限公司

Applicant(s)

号 (Eneral General







發文日期: 西元 <u>2004</u>年 <u>4</u> 月 <u>5</u>日 Issue Date

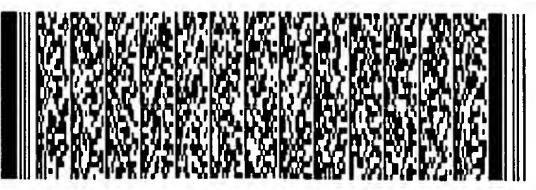
發文字號: / 09320308600 Serial No.

申請日期:	IPC分類
申請案號:	

以上各欄	由本局填言	發明專利說明書
	中文	一種蝕刻液組成
簽明名稱	英 文	ETCHANT COMPOSITION FOR SEM IMAGE ENHANCEMENT OF P-N JUNCTION CONTRAST
	姓 名 (中文)	1. 張少康
=	姓 名 (英文)	1. CHANG, SHAO-KANG
發明人	國籍(中英文)	1. 中華民國 TW
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	住居所(英文)	1. No. 17, Alley 4, Alley 18, Lane 142, Sec. 1, Shuen-Lien, Ming-tsuRd., Pin-Chen City, Tao-Yuan Hsien, Taiwan, R.O.C.
	名稱或 姓 名 (中文)	1. 南亞科技股份有限公司
	名稱或 姓 名 (英文)	1. NANYA TECHNOLOGY CORP.
Ξ	國籍(中英文)	1. 中華民國 TW
申請人 (共1人)		1. 桃園縣龜山鄉華亞科技園區復興三路六六九號
	住居所 (營業所) (英 文)	1. HWA-YA TECHNOLOGY PARK 669, FUHSING 3 RD., KUEISHAN, Tao-Yuan Hsien, Taiwan, R.O.C.
	代表人(中文)	1. 連日昌
	代表人(英文)	1. LIEN, JIH

申請日期:	IPC分類	
申請案號:		
		رام ہے۔

	**	
(以上各欄)	由本局填	發明專利說明書
	中文	
發明名稱	英文	
	姓 名 (中文)	2. 莊景誠 3. 陳逸男
<u>-</u>	(英文)	2. CHUANG, GRAHAM 3. CHEN, YI-NAN
發明人 (共3人)	國 籍 (中英文)	2. 中華民國 TW 3. 中華民國 TW
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	住居所 (英 文)	2.2F, No. 68, Chang Keng Yi Hu Hsin Tsun, Kuei-Shen Hsiang, Tao-Yuan Hsien, Taiwan, R.O.C. 3.No. 4, Lane 151, Chien-Min Rd., Pei-Tou, Taipei City, Taiwan,
	名稱或 姓 名 (中文)	R. O. C.
	名稱或 姓 名 (英文)	
= ,	國籍(中英文)	
申請人(共1人)	住居所 (營業所) (中 文)	
	住居所 (營業所) (英 文)	
	代表人(中文)	
	代表人 (英文)	
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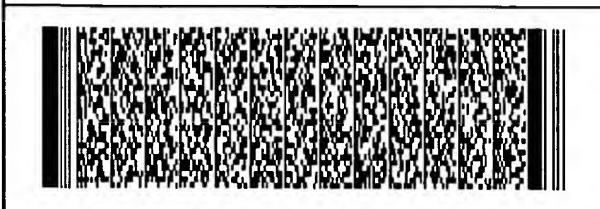


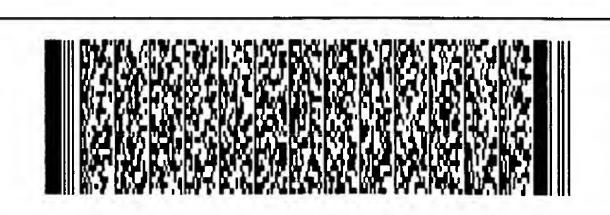
四、中文發明摘要 (發明名稱:一種蝕刻液組成)

本發明揭露一種SEM試片預處理蝕刻液組成,包含有NTC-1號溶液,其為含有機酸/氫氟酸/硝酸(HNO3)之A劑再與濃度49%之氫氟酸混合而成;以及NTC-2號溶液含有金屬離子以及強氧化劑;其中該NTC-1號溶液與該NTC-2號溶液係以特定體積比例混合。SEM試片在進行分析之前,先浸入本發明之獨特SEM試片預處理蝕刻液組成配方中,即可獲得半導體元件基底中之P-N接面清晰輪廓。

五、英文發明摘要 (發明名稱:ETCHANT COMPOSITION FOR SEM IMAGE ENHANCEMENT OF P-N JUNCTION CONTRAST)

An etchant composition for SEM image enhancement of P-N junction contrast is disclosed. The composition comprises an NTC-1 solution mixed with an NTC-2 solution at a selected volumetric ratio. The NTC-1 solution is prepared by mixing A solution comprising organic acid, HF, and nitric acid with 49% HF solution. The NTC-2 solution comprises metal ions and a





四、中文發明摘要 (發明名稱:一種蝕刻液組成)

五、英文發明摘要 (發明名稱: ETCHANT COMPOSITION FOR SEM IMAGE ENHANCEMENT OF P-N JUNCTION CONTRAST)

strong oxidant. After the preparation of the NTC-1/NTC-2 solution, they are mixed together at specific volumetric ratio. Before carrying out a SEM analysis, the SEM specimen is dipped into the etchant composition.



六、指定代表圖

- (一)、本案代表圖為:第圖
- (二)、本案代表圖之元件代表符號簡單說明 本申請案無圖式



一、本案已向			
國家(地區)申請專利	申請日期	案 號	主張專利法第二十四條第一項優先和
		·	
		無	
二、□主張專利法第二十	五條之一第一項係	多先權·	
申請案號:		ζ) Ο Ιμ.	
		無	
日期:			
三、主張本案係符合專利	法第二十條第一項	頁□第一款但書	或□第二款但書規定之期間
日期:			
四、□有關微生物已寄存	於國外:		
寄存國家: 寄存機構:		無	
可行機構· 寄存日期:			
寄存號碼:		>	
□有關微生物已寄存 寄存機構:	·於國內(本局所指	定之寄存機構)	:
寄存日期:		無	
寄存號碼:	سل جاد جود سب التاد خادر در		
□熟習該項技術者易	於獲得,不須寄存	0	

五、發明說明 (1)

發明所屬之技術領域

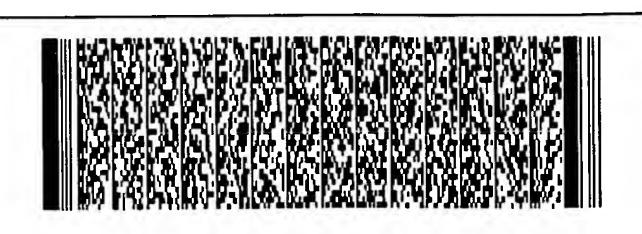
本發明係關於一種蝕刻液(etchant)組成,尤指一種應用在掃瞄式電子顯微鏡(Scanning Electron Microscopy, SEM)技術中可用以顯現出半導體元件基底中之P-N接面輪廓的SEM試片預處理蝕刻液組成。

先前技術

如該行業者所熟知,在半導體元件分析技術中,掃瞄式電子顯微鏡(SEM)可用來分析積體電路剖面結構,例如,對於溝渠式動態記憶體元件而言,掃瞄式電子顯微鏡觀察以觀察溝渠電容結構。習知利用掃瞄式電子顯微鏡觀察溝渠式動態記憶體元件的溝渠電容剖面結構影像前,通常需要將試片(specimen)預先浸入一種蝕刻酸液中,例如業界所通稱的Oki酸或Flou酸,用以侵蝕溝渠電容中的多晶矽,以方便在掃瞄式電子顯微鏡分析過程中形成清晰的對比影像。其中,如熟習該項技藝者所知,Oki酸的配方係為體積比200:1的硝酸: 49%氫氟酸(HF)。

在某些情況下,利用掃瞄式電子顯微鏡觀察溝渠電容結構的同時,若能夠在照片中顯現出P-N接面輪廓更好。然而,上述習知前處理酸液卻無法達到如此的功效。鑑於此,申請人乃結合學理及多年累積之工作經驗法則研發





五、發明說明 (2)

出一種可使半導體元件基底中之P-N接面剖面輪廓可以透一過掃瞄式電子顯微鏡獲得清晰觀察之獨特配方。

發明內容

本發明之主要目的在於提供一種可使半導體元件基底中之P-N接面輪廓得透過掃瞄式電子顯微鏡獲得清晰觀察之獨特SEM試片預處理蝕刻液組成配方。

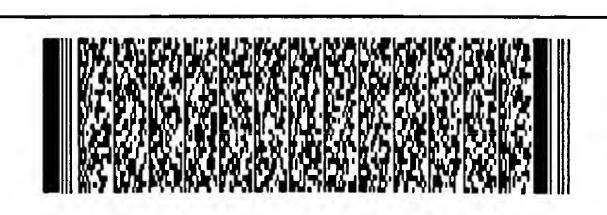
根據本發明之較佳實施例,本發明揭露一種蝕刻液組成,包含有NTC-1號溶液,其為含有機酸/氫氟酸/硝酸(HNO₃)之A劑再與濃度49%之氫氟酸混合而成;以及NTC-2號溶液含有金屬離子以及強氧化劑;其中該NTC-1號溶液與該NTC-2號溶液係以特定體積比例混合。

為了使 貴審查委員能更近一步了解本發明之特徵及技術內容,請參閱以下有關本發明之詳細說明與附圖。然而所附圖式僅供參考與輔助說明用,並非用來對本發明加以限制者。

實施方式

本發明之一種可使半導體元件基底中之P-N接面輪廓得透過掃瞄式電子顯微鏡獲得清晰觀察之獨特SEM試片預處理





五、發明說明 (3)

蝕刻液組成配方係由兩種預先掺配之溶液以特定體積比例混合而成,以下分別稱為NTC-1號溶液以及NTC-2號溶液。

根據本發明之較佳實施例,NTC-1號溶液含有體積比由 1:1:4至1:1:25範圍之有機酸:氫氟酸:硝酸(HNO₃)之A 劑再以體積比2:1至5:1之比例與濃度49%之氫氟酸混合而成。其中,有機酸可以為蟻酸(formic acid)、醋酸(HAC)、丙酸等,較佳為醋酸。NTC-2號溶液含有金屬離子以及強氧化劑。金屬離子可為銅離子、鎂離子、鋁離子、鈣離子、鋅離子等,又以銅離子較佳。強氧化劑可以為雙氧水、臭氧、硫酸等等,而以硫酸(sulfuric acid)較佳。依據本發明之較佳實施例,NTC-2號溶液係將0.005M至0.02M之硝酸銅溶液以體積比2:1至5:1之比例與硫酸(90%)溶液混合而成。

本發明之一種可使半導體元件基底中之P-N接面輪廓得透過掃瞄式電子顯微鏡獲得清晰觀察之獨特SEM試片預處理蝕刻液組成配方係將上述兩種預先掺配之溶液:NTC-1號溶液以及NTC-2號溶液,以特定體積比例混合而成。依據本發明之較佳實施例,NTC-1號溶液以及NTC-2號溶液之紀合比例介於體積比1:1至1:5之間。SEM試片在進行分析之前,先浸入本發明之獨特SEM試片預處理蝕刻液組配方中,即可獲得半導體元件基底中之P-N接面清晰輪





五、發明說明 (4)

廓。

以上所述僅為本發明之較佳實施例,凡依本發明申請專利範圍所做之均等變化與修飾,皆應屬本發明專利之涵蓋範圍。



圖式簡單說明

圖式之簡單說明

本申請案無圖式

圖式之符號說明

本申請案無符號說明



六、申請專利範圍

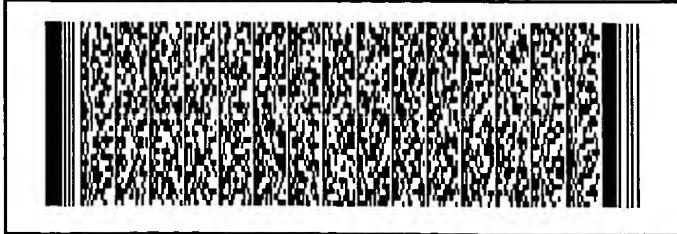
1. 一種蝕刻液組成,包含有:

NTC-1號溶液,其為含有機酸/氫氟酸/硝酸(HNO3)之A劑再與濃度49%之氫氟酸混合而成;以及

NTC-2號溶液含有金屬離子以及強氧化劑;

其中該NTC-1號溶液與該NTC-2號溶液係以特定體積比例混合。

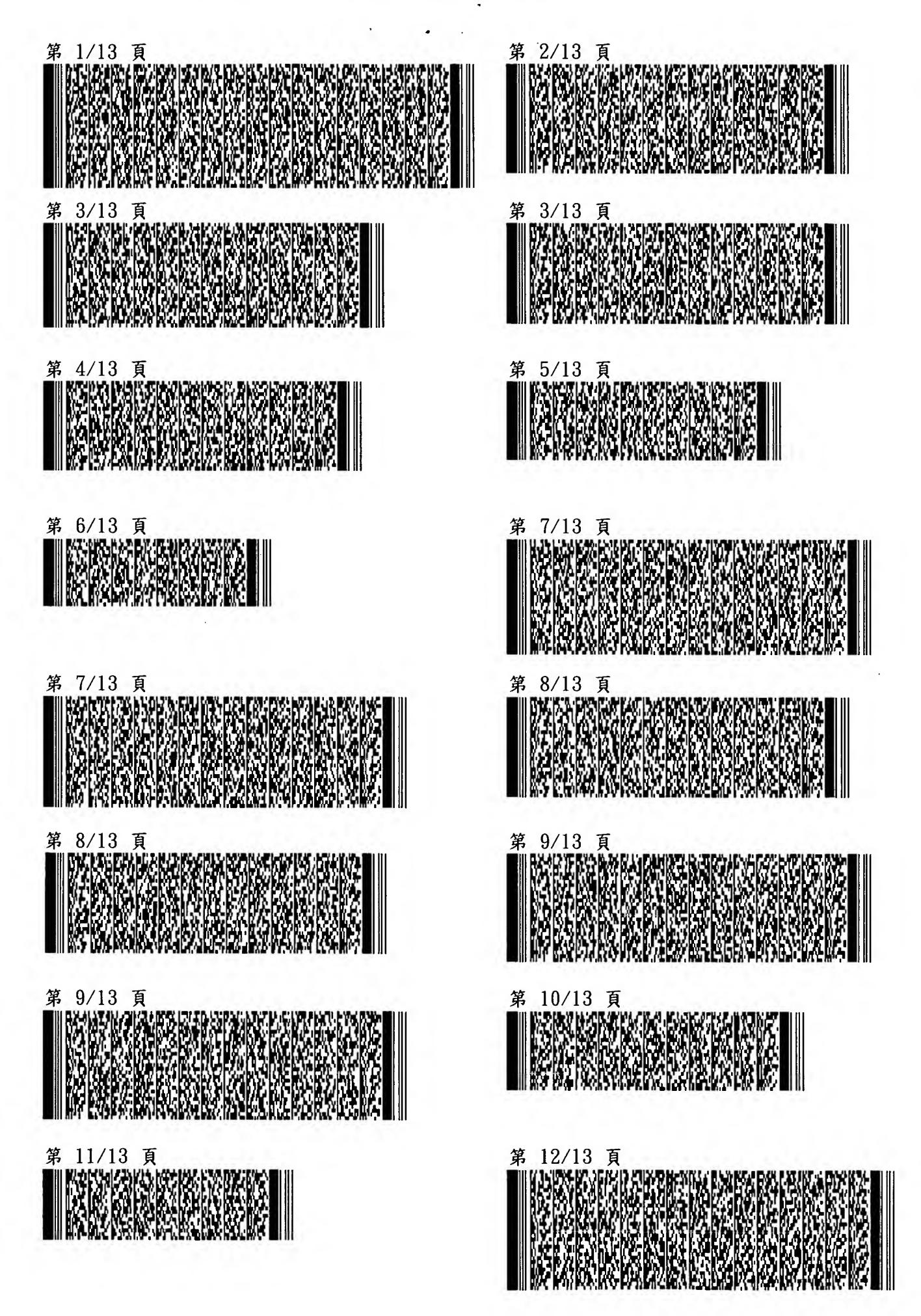
- 2. 如申請專利範圍第1項所述之蝕刻液組成,其中該A劑所含之有機酸:氫氟酸:硝酸(HNO_3),其體積比由1:1:4至1:1:25範圍。
- 3. 如申請專利範圍第1項所述之蝕刻液組成,其中該A劑與該氫氟酸以體積比2:1至5:1之比例混合。
- 4. 如申請專利範圍第1項所述之蝕刻液組成,其中該有機酸包含蟻酸(formic acid)、醋酸(HAc)及丙酸。
- 5. 如申請專利範圍第1項所述之蝕刻液組成,其中該金屬離子包含銅離子、鎂離子、鋁離子、鈣離子及鋅離子。
- 6.如申請專利範圍第1項所述之蝕刻液組成,其中該強氧化劑包含雙氧水、臭氧及硫酸。
- 7. 如申請專利範圍第1項所述之蝕刻液組成,其中該NTC-



六、申請專利範圍

- 2號溶液係將0.005M至0.02M之硝酸銅溶液以體積比2:1至5:1之比例與硫酸(90%)溶液混合而成。
- 8. 如申請專利範圍第1項所述之蝕刻液組成,其中該NTC-1號溶液以及NTC-2號溶液之混合比例介於體積比1:1至1:5之間。





(4.7版)申請案件名稱:一種蝕刻液組成

